

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

T. SEKI et al

Serial No.

Filed: January 10, 2001

For: ION IMPLANTATION EQUIPMENT AND
IMPLANTATION METHOD THEREOF

PRELIMINARY AMENDMENT

Assistant Commissioner of Patents
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified
patent application as follows.

IN THE CLAIMS

Please amend claim 3 as follows.

3. (Amended) An ion implantation equipment as defined
in claim[s] 1 [and 2], wherein

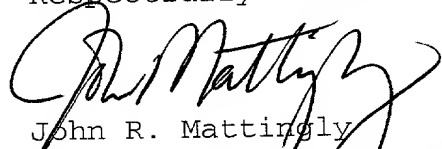
said scanning means for putting together a scanning
surface of said ion beam with a deflection surface of said ion
beam deflected by said mass separation means.

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REMARKS

Examination is requested.

Respectfully submitted,



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